T 37	Hits	Search Text	DB	Time stamp
L Number	18	(((slop\$3 or inclin\$3 or taper\$3) with	USPAT;	2004/04/20 16:19
1	10	(etch\$3)) and 430/320.ccls.) not	US-PGPUB;	
		((((resist or photoresist) and (slop\$3 or	EPO; JPO;	
ļ		inclin\$3 or taper\$3)) with (etch\$3)) and	IBM_TDB	
		((grey or gray) same (mask or reticle)))		
		not (((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same		
		(etch\$3)) and ((grey or gray) same		
		(photomask or mask or reticle))) not		
		((((resist or photoresist) and (slop\$3 or		
		inclin\$3 or taper\$3)) with (etch\$3)) and		
		((grey or gray) same (photomask or mask or		
		reticle)))) not (430/314,323-324.ccls. not		
		((((resist or photoresist) and (slop\$3 or		
		inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or		
		reticle))) not (((((resist or photoresist)		
		and (slop\$3 or inclin\$3 or taper\$3)) same		
		(etch\$3)) and ((grey or gray) same		
		(photomask or mask or reticle))) not		
		((((resist or photoresist) and (slop\$3 or	1	
		inclin\$3 or taper\$3)) with (etch\$3)) and		·
		((grey or gray) same (photomask or mask or		
		reticle))))) not (((mems or moems or microelectromechanical or micro adj		
		electromechanical).ti.ab.) and (microbeam		
1		or microplatform or microsupport or		
		(suspend\$3 with microstructure))) not		
		((((photolithograph\$6 or lithograph\$6 or		
		photoresist or resist) and etch\$3 and		
		(204/192.14-192.15,192.17,192.23,192.25 or		
		205/122-123,125).ccls.) not		
		430/314,323-324.ccls.) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or		
		taper\$3)) with (etch\$3)) and ((grey or		
		gray) same (mask or reticle)))) not		
		(resistive adj evaporat\$3 and		
		((photolithograph\$6 or photoresist or		
		resist) same etch\$3)) not		
		(430/314,323-324.ccls. and (planarization		
		adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with		
		(etch\$3)) and ((grey or gray) same		
1		(photomask or mask or reticle))) not		
		((((resist or photoresist) and (slop\$3 or		
		inclin\$3 or taper\$3)) same (etch\$3)) and		
		((grey or gray) same (photomask or mask or		
		reticle))) not ((((resist or photoresist)		
		and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same		
		(photomask or mask or reticle)))) not		
		((resist or photoresist) and (air adj		
Į		bridge same (slop\$3 or inclin\$3 or		
		taper\$3))) not ((resist or photoresist)		
		and ((microbeam) same (slop\$3 or inclin\$3		
		or taper\$3)))	USPAT;	2004/04/20 16:19
2	3	(resist or photoresist) and ((microbeam)	US-PGPUB;	2004/04/20 10.13
		same (slop\$3 or inclin\$3 or taper\$3))	EPO; JPO;	
			IBM TDB	
3	1	((resist or photoresist) and	USPAT;	2004/04/20 16:20
	1	((microplatform or suspend\$3) same (slop\$3	US-PGPUB;	
		or inclin\$3 or taper\$3))) and ((grey or	EPO; JPO;	
		gray) with mask)	IBM_TDB	2004/04/20 16:20
4	14	(resist or photoresist) and (air adj	USPAT; US-PGPUB;	2004/04/20 16:20
		bridge same (slop\$3 or inclin\$3 or	EPO; JPO;	
		taper\$3))	IBM TDB	
l <sub>v</sub>	1			

		1 / 1	DODAM.	2004/04/20 16:22
5	36	430/314,323-324.ccls. and (planarization adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/04/20 16:22
		<pre>(etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3 or</pre>	164_105	
		<pre>inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or</pre>		
		reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same		
6	. 19	(photomask or mask or reticle)))) resistive adj evaporat\$3 and	USPAT;	2004/04/20 16:23
		((photolithograph\$6 or photoresist or resist) same etch\$3)	US-PGPUB	
7	979	(((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and	USPAT; US-PGPUB;	2004/04/20 16:25
		(204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not (((resist or	EPO; JPO; IBM_TDB	
		photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or		
8	45	gray) same (mask or reticle))) ((mems or moems or microelectromechanical	USPAT; US-PGPUB;	2004/04/20 16:29
		or micro adj electromechanical).ti.ab.) and (microbeam or microplatform or microsupport or (suspend\$3 with microstructure))	EPO; JPO; IBM_TDB	
9	3264	430/314,323-324.ccls. not ((((resist or photoresist) and (slop\$3 or inclin\$3 or	USPAT; US-PGPUB;	2004/04/20 16:32
		taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist)	EPO; JPO; IBM_TDB	
		and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same		
		<pre>(photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and</pre>		
		((grey or gray) same (photomask or mask or reticle))))	ana	0004/04/00 17 01
10	30	((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or	USPAT; US-PGPUB; EPO; JPO;	2004/04/20 17:01
		reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with	IBM_TDB	
11	57	<pre>(etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) (((resist or photoresist) and (slop\$3 or</pre>	USPAT;	2004/04/20 17:02
- 50 -		<pre>inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))</pre>	US-PGPUB; EPO; JPO; IBM TDB	
_	830	(((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) and (etch\$3)) and (grey or gray)	USPAT; US-PGPUB; EPO; JPO;	2003/01/24 16:24
_	35	(((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/01/31 16:54
_	0	<pre>(((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))</pre>	IBM_TDB DERWENT	2003/07/22 15:32
_	0	not us.pc. (430/314,323-324.ccls. not ((((resist or photoresist) and (slop\$3 or inclin\$3 or	DERWENT	2003/07/22 15:32
-	2920	taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))) not us.pc. 430/314,323-324.ccls. not (((resist or	USPAT;	2003/01/17 17:08
		photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))	US-PGPUB; EPO; JPO; IBM_TDB	

-	6	(("5962909") or ("5831266") or ("6130109") or ("6025951") or ("6201243") or ("20020043706")).PN.	USPAT; US-PGPUB	2003/01/17 09:20
	35	(((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and	USPAT; US-PGPUB;	2003/01/17 15:37
		((grey or gray) same (photomask or mask or reticle))	EPO; JPO; IBM_TDB USPAT;	2003/01/17 15:37
	29	(((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) with (photomask or mask or	US-PGPUB; EPO; JPO;	2003/01/17 13.37
_	58	reticle)) (((resist or photoresist) and (slop\$3 or	IBM_TDB USPAT; US-PGPUB;	2003/01/17 15:41
		<pre>inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))</pre>	EPO; JPO; IBM TDB	
-	23	((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or	USPAT; US-PGPUB; EPO; JPO;	2004/01/31 16:55
		reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with	IBM_TDB	
	2010	<pre>(etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) 430/314,323-324.ccls. not (((resist or</pre>	USPAT;	2004/01/31 16:57
_	2919	<pre>photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or</pre>	ÚS-PGPUB; EPO; JPO;	2004/01/31 10.37
		<pre>gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same</pre>	IBM_TDB	
		<pre>(etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not</pre>		
		((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or		
-	623	reticle)))) (mems or moems or microelectromechanical or micro adj electromechanical).ti.ab.	USPAT; US-PGPUB; EPO; JPO;	2003/01/18 11:46
_	26	((mems or moems or microelectromechanical	IBM_TDB USPAT;	2004/01/31 16:58
		or micro adj electromechanical).ti.ab.) and (microbeam or microplatform or microsupport or (suspend\$3 with	US-PGPUB; EPO; JPO; IBM TDB	
_	884	microstructure)) (photolithograph\$6 or lithograph\$6 or	USPAT;	2003/01/18 13:38
		photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.	US-PGPUB	
-	827	((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not	USPAT; US-PGPUB	2003/01/18 13:39
_	827	430/314,323-324.ccls. (((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and	USPAT; US-PGPUB;	2004/01/31 17:04
		(204/192:14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not (((resist or	EPO; JPO; IBM_TDB	
		photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or		
-	17	gray) same (mask or reticle))) resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or	USPAT; US-PGPUB	2004/01/31 17:05
-	6636	resist) same etch\$3) electroplat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3)	USPAT; US-PGPUB	2003/01/20 15:35

		420/014 202 204 l- and /planamigation	USPAT;	2004/01/31	17.06
-	34	430/314,323-324.ccls. and (planarization		2004/01/31	17:00
		adj layer) not ((((resist or photoresist)	US-PGPUB;		
		and (slop\$3 or inclin\$3 or taper\$3)) with	EPO; JPO;		
		(etch\$3)) and ((grey or gray) same	IBM_TDB		
		(photomask or mask or reticle))) not			
1		(((((resist or photoresist) and (slop\$3 or			
		inclin\$3 or taper\$3)) same (etch\$3)) and			
		((grey or gray) same (photomask or mask or			
		reticle))) not ((((resist or photoresist)			
		and (slop\$3 or inclin\$3 or taper\$3)) with			
		(etch\$3)) and ((grey or gray) same			
		(photomask or mask or reticle))))			
	440	(resist or photoresist) and (air adj	USPAT;	2003/01/23	17:03
-	440	bridge)	US-PGPUB;	2000,01,20	
		briage;	EPO; JPO;		
			IBM TDB		
	0.1.0	(	USPAT;	2003/01/23	17.04
-	210	(resist or photoresist) same (air adj		2003/01/23	17:04
		bridge)	US-PGPUB;		
			EPO; JPO;		
			IBM_TDB		
-	10	(resist or photoresist) and (air adj	USPAT;	2004/01/31	17:06
		bridge same (slop\$3 or inclin\$3 or	US-PGPUB;		
		taper\$3))	EPO; JPO;		i
			IBM_TDB		
-	1	((resist or photoresist) and	USPAT;	2004/01/31	17:08
		((microplatform or suspend\$3) same (slop\$3	US-PGPUB;		ŀ
		or inclin\$3 or taper\$3))) and ((grey or	EPO; JPO;		
		gray) with mask)	IBM TDB		
_	2	(resist or photoresist) and ((microbeam)	USPAT;	2004/01/31	17:08
	_	same (slop\$3 or inclin\$3 or taper\$3))	US-PGPUB;		
		James (Saspie SI IIIIIII)	EPO; JPO;		
			IBM TDB		
	900	(resist or photoresist) and	USPAT;	2003/01/24	11:20
-	] 300	((microplatform or suspend\$3) same (slop\$3	US-PGPUB;	2005,01,24	11.20
			EPO; JPO;		
		or inclin\$3 or taper\$3))	IBM TDB		
			T DM T DB	Ť	

Page 4

[((slops8) or inclin8) or tager83) with (etch83) and (((resist or photoresist) and (slop83 or inclin8) or taper83)) with (etch83) and ((apey or gray) same (mask or reticle)) not (((((resist or photoresist) and (slop83 or inclin8) or taper83)) with (etch83)) and ((apey or gray) same (photomask or mask or reticle)) not ((((resist or photoresist) and (slop83 or inclin83 or taper83)) with (etch83)) and (((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop83 or inclin83 or taper83)) with (etch83)) and (((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop8) or inclin83 or taper83)) with (etch83)) and (((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop8) or inclin83 or taper83)) with (etch83)) and (((grey or gray) same (((((grey or gray) same ((((((grey or gray) same ((((((((((((((((((((((((((((((((((((
((tresist or photoresist) and (slops3 or inclin\$3 or taper\$3)) with (atch\$3)) and ((grey or gray) same (mask or reticle)) not ((((tresist or photoresist) and (slops3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (mask or reticle)) not ((((tresist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (atch\$3) and ((grey or gray) same (photomask or mask or reticle)) not ((((tresist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (atch\$3) and ((grey or gray) same (photomask or mask or reticle)) not ((((tresist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (atch\$3)) and ((grey or gray) same (photomask) or mask or reticle)) not ((((tresist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (atch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((tresist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (atch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not ((((special or microsupport or (suspend\$3 with microstructure))) not ((((photolithograph\$6 or lithograph\$6 or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (atch\$3) and ((grey or gray) same (photomask or mask or reticle))) not ((((photolithograph\$6 or lithograph\$6 or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (atch\$3) and ((grey or gray) same (mask or reticle)))) not (((csist or photoresist)) and ((photolithograph\$6 or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (ctch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist)) and ((grey or gray) same (photomask or mask or taper\$3)) with (ctch\$3)) and ((grey or gray) same (photomask or mask or taper\$3)) with (ctch\$3)) and ((grey or gray) same (photomask or mask or taper\$3)) with (ctch\$3)) and ((grey or gray) same (photomask or mask or taper\$3)) with (ctch\$3)) and ((grey or gray) same (photomask or mask or taper\$3)) with (ctch\$3)) and ((grey or gray) same (photomask or mask or taper\$3)) or taper\$3)) or taper\$3)) or taper\$3) and (microbeam) same (slop\$3 or
inclins3 or tapers3) with (etchs3) and ((grey or gray) same (nask or reticle)) not (((((resist or photoresist) and (slop\$3 or inclins3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclins3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist)) and (slop\$3 or inclin\$3 or taper\$3)) same (photomask or mask or reticle)))) not ((((resior or photoresist)) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not ((((resior or photoresist)) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not ((((photolithograph\$6 or inclin\$3 or decharaction or microsupport or (suspend\$3 with microstructure))) not ((((photolithograph\$6 or inclin\$3 or decharaction or microsupport or (suspend\$3 with microstructure))) not ((((photolithograph\$6 or inclin\$3 or decharaction or microsupport or (suspend\$3 with microstructure))) not ((((photolithograph\$6 or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (etch\$3)) not ((grey or gray) same (etch\$3)) and ((grey or gray) same (etch\$3)) and ((grey or gray) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((cresist or photoresist)) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and (grey or gray) same (etch\$3)) and ((grey or gray) same (etch\$3)) and ((grey or gray) same (etch\$3)) and ((grey or gray) same (etch\$3)) and (grey or gray) same (etch\$3)) and (grey or gray) same (etch\$3)) and (grey or gray) same (etch\$3) and (grey or gray) same (etch\$3)) and (grey or gray) same (gray) or
(((grey) or gray) same (mask or reticle))  not ((((fesist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$1)) and ((grey or gray) same (photomask or mask or reticle))) not (((fesist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not (430/314,323-324.ccls. not (((fesist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((fesist or photoresist)) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((fesist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not (((mens or momes or microelectromechanical or micro adj electromechanical) or micro adj electromechanical), i.a.b. and (microbeam or microplatform or microsupport or (suspend\$3 with microstructure))) not ((((photolithograph\$6 or lithograph\$6 or photoresist) and etch\$3 and ((204/192,14-192,15,192,17,192,23,192,25 or 205/122-123,125).ccls.) not 430/314,323-324.ccls.) not (((resist or photoresist or resist) same etch\$3)) not (resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3)) not ((grey or gray) same (photomask or mask or reticle))) not ((((fesist or photoresist)) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (allop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and (grey or gray) same (photomask or mask or reticle)))) not ((resist or photoresist) and (allop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) not ((resist or photoresist) and (microbeam) same (slop\$3 or inclin\$3 or taper\$3)))  ((resist or photor
not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$31) same (etch\$31) and ((grey or gray) same (photomask or mask or reticle)) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$31) with (etch\$31) and ((grey or gray) same (photomask or mask or reticle))) not (430/314, 233-324.ccls. not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$31) with (etch\$31) and ((grey or gray) same (photomask or mask or reticle)) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$31) same (photomask or mask or reticle)) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$31) with (etch\$31) and ((grey or gray) same (photomask or mask or reticle)) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$31) with (etch\$31) and ((grey or gray) same (photomask or mask or reticle)))) not (((mens or moems or microelectromechanical or micro adj electromechanical).ti.ab.) and (microbeam or microplatform or microsupport or (suspend\$3 with microstructure))) not (((ghotolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 or 205/122-123,125).ccls.) not 430/314,223-224.ccls.) not (((resist or photoresist)) and (slop\$3 or inclin\$3 or taper\$31) with (etch\$31) and ((grey or gray) same (mask or reticle))) not (resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$31) not ((30/314,323-324.ccls.) and (ling\$3 or inclin\$3 or taper\$31) same (etch\$31) and ((grey or gray) same (photomask or mask or reticle)) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$31) with (etch\$31) and ((grey or gray) same (photomask or mask or reticle)))) not ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$31) with (etch\$31) and (or gray) same (photomask or mask or reticle)))) not ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$31) with (etch\$31) not ((resist or photoresist) and (microbeam) same (slop\$3 or inclin\$3 or taper\$31)) not ((resist or photoresist) and (microbeam) same (slop\$3 or inclin\$3 or taper\$31)) not (resist or photores
(stop\$3 or inclin\$3 or taper\$3)) same (stoch\$3)) and ((grey or gray) same (photomask or mask or reticle)) not ((((resist or photomessist) and (slop\$3 or inclin\$3 or taper\$3)) with (stoch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not (\$30/314,323-324.ccls. not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (stoch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist)) and (slop\$3 or inclin\$3 or taper\$3)) same (stoch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (stoch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not (((mens or moems or microelectromechanical or micro adj electromechanical) ti.ab.) and (microbeam or microplatform or microsupport or (suspend\$3 with microstructure)) not ((((shotolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not (30/314,223-324.ccls.) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (stch\$3)) and ((grey or gray) same (mask or reticle))) not (resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3) not (430/314,323-324.ccls. and (planarization adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and (grey or gray) same (photomask or mask or reticle)))) not ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) not ((grey or gray) same (photomask or mask or reticle))) not (resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) not (gray or gray) same (slop\$3 or inclin\$3 or taper\$3)) not ((resist or photoresist) and (microbeam) s
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((photomask or mask or reticle)) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$31) with (etch\$3) and ((grey or gray) same (photomask or mask or reticle))) not (430/314,323-324.ccls. not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))))) not ((((grey or gray) same (photomask or mask or reticle))))) not ((((grey or gray) same (photomask or mask or reticle))))) not ((((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not (30/314,323-324.ccls.) not (430/314,323-324.ccls.) not (((resist or photoresist) or resist) and (qrey or gray) same (mask or reticle)))) not (resist) same etch\$3)) not (430/314,323-324.ccls. and (planarization and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not (((((resist or photoresist) and (slop\$3 or inclin\$3 or tresist) same etch\$3)) not (((((resist or photoresist)) not (((resist or photoresist)) and ((grey or gray) same (bhotomask or mask or reticle))) not ((((resist or photoresist)) not ((((resist or photoresist)) and (alr adj bridge same (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not ((resist or photoresist) and (alr adj bridge same (slop\$3 or inclin\$3 or taper\$3))) not ((resist or photoresist) and (alr adj bridge same (slop\$3 or inclin\$3 or taper\$3))) not ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3) and ((grey or gray) same (mask or reticle)))  (IRM_TDB
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inclin§3 or taper§3)) with (etch§3) and ((grey or gray) same (photomask or mask or reticle))) not (430/314,323-324.ccls. not (((tresist or photoresist) and (slop§3 or inclin§3 or taper§3)) with (etch§3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop§3 or inclin§3 or taper§3)) same (etch§3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop§3 or inclin§3 or taper§3)) with (etch§3)) and ((grey or gray) same (photomask or mask or reticle)))) not (((grey or gray) same (photomask or mask or reticle)))) not (((mems or moems or microelectromechanical).ti.ab.) and (microbeam or microelectromechanical).ti.ab.) and (microbeam or microplatform or microsupport or (suspend§3 with microstructure))) not ((((photolithograph§6 or lithograph§6 or photoresist or resist) and etch§3 and (204/192.14-192.15,192.21,192.23,192.25 or 205/122-123,125).ccls.) not 430/314,323-324.ccls.) not ((((resist or photoresist)) and (slop§3 or inclin§3 or taper§3)) with (etch§3)) and ((grey or gray) same (mask or reticle)))) not (resistive and (slop§3 or inclin§3 or taper§3)) with (etch§3)) and ((photolithograph§6 or photoresist) and ((photolithograph§6 or photoresist) and ((photolithograph§6 or photoresist) and ((photolithograph§6 or photoresist) and ((photomask or mask or raper§3)) with (etch§3)) and ((grey or gray) same (etch§3)) and ((grey or gray) same (photomask or mask or raper§3)) with (etch§3) and ((grey or gray) same (slop§3 or inclin§3 or taper§3)) with (etch§3)) and ((grey or gray) same (slop§3 or inclin§3 or taper§3)) mot ((resist or photoresist) and (air adj bridge same (slop§3 or inclin§3 or taper§3)) not ((resist or photoresist) and (air adj bridge same (slop§3 or inclin§3 or
((grey or gray) same (photomask or mask or reticle))) not (430/314,323-324.ccls. not (((tresist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((mems or moems or microelectromechanical) or micro adj electromechanical) i.i. ab.) and (microbeam or microplatform or microsupport or (suspend\$3 with microstructure)) not ((((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not 430/314,323-324.ccls.) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))) not (resistive adj evaporat\$3 and (photolithograph\$6 or photoresist or resist) same etch\$3)) not ((330/314,323-324.ccls. and (planarization adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and (grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and (grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and (grey or gray) same (photomask or mask or reticle))) not ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and (grey or gray) same (photomask or mask or reticle))) not ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and (grey or gray) same (photomask or mask or reticle))) not (grey or gray) same (photomask or mask or reticle))) not (grey or gray) same (photomask)
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photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not 430/314,323-324.ccls.) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))) not (resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3)) not ((300/314,323-324.ccls. and (planarization adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not ((resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3))) not ((resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3)))  - 45 (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3))) with (etch\$3)) and ((grey or gray) same (mask or reticle))  USPAT;  USPAT;  USPAT;  USPAT;  POG JPO; IBM_TDB
(204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))) not (resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3)) not (430/314,323-324.ccls. and (planarization adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))))) not ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))))) not ((resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3))) not ((resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3))) (((resist or photoresist) and (Slop\$3 or inclin\$3 or taper\$3))) with (etch\$3)) and ((grey or gray) same (mask or reticle))) Inclin\$3 or taper\$3)) with (etch\$3) and ((microbeam) same (slop\$3 or inclin\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and (microbeam) same (slop\$3 or inclin\$3 or inclin\$3 or taper\$3)) with (etch\$3) and (microbeam) same (slop\$3 or inclin\$3 or inclin\$3 or inclin\$3 or taper\$3)) with (etch\$3) and (microbeam) same (slop\$3 or inclin\$3 or
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taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))) not (resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3)) not ((430/314,323-324.ccls. and (planarization adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))))) not ((resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3))) not ((resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3))) (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3))) (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3))) with (etch\$3)) and ((grey or gray) same (mask or reticle)) USPAT; (SPAT; IBM_TDB)
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<pre>((photolithograph%6 or photoresist or resist) same etch%3)) not (430/314,323-324.ccls. and (planarization adj layer) not ((((resist or photoresist) and (slop%3 or inclin%3 or taper%3)) with (etch%3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop%3 or inclin%3 or taper%3)) same (etch%3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop%3 or inclin%3 or taper%3)) with (etch%3)) and ((grey or gray) same (photomask or mask or reticle))))) not ((resist or photoresist) and (air adj bridge same (slop%3 or inclin%3 or taper%3))) not ((resist or photoresist) and ((microbeam) same (slop%3 or inclin%3 or taper%3)))  (((resist or photoresist) and (slop%3 or inclin%3 or taper%3)) with (etch%3)) and ((grey or gray) same (mask or reticle))  EPO, JPO; IBM_TDB</pre>
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adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not ((resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3))) not ((resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3)))  45 ((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))  EPO; JPO; IBM_TDB
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<pre>(etch\$3)) and ((grey or gray) same   (photomask or mask or reticle))) not   (((((resist or photoresist) and (slop\$3 or   inclin\$3 or taper\$3)) same (etch\$3)) and   ((grey or gray) same (photomask or mask or   reticle))) not ((((resist or photoresist)   and (slop\$3 or inclin\$3 or taper\$3)) with   (etch\$3)) and ((grey or gray) same   (photomask or mask or reticle))))) not   ((resist or photoresist) and (air adj   bridge same (slop\$3 or inclin\$3 or   taper\$3))) not ((resist or photoresist)   and ((microbeam) same (slop\$3 or inclin\$3   or taper\$3)))   (((resist or photoresist) and (slop\$3 or   inclin\$3 or taper\$3)) with (etch\$3)) and   ((grey or gray) same (mask or reticle))   [EPO; JPO;   IBM_TDB</pre>
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<pre>((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))) not ((resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3))) not ((resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3)))  (((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle))  EPO; JPO; IBM_TDB</pre>
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<pre>(etch\$3)) and ((grey or gray) same</pre>
<pre>(photomask or mask or reticle))))) not   ((resist or photoresist) and (air adj   bridge same (slop\$3 or inclin\$3 or   taper\$3))) not ((resist or photoresist)   and ((microbeam) same (slop\$3 or inclin\$3   or taper\$3)))  - 45 (((resist or photoresist) and (slop\$3 or uspar; 2004/01/31 17:   inclin\$3 or taper\$3)) with (etch\$3)) and (slop\$3 or uspar; 2004/01/31 17:   inclin\$3 or taper\$3)) with (etch\$3)) and (slop\$3 or uspar; 2004/01/31 17:   inclin\$3 or taper\$3)</pre>
<pre>((resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3))) not ((resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3)))  - 45 (((resist or photoresist) and (slop\$3 or uspar; 2004/01/31 17: inclin\$3 or taper\$3)) with (etch\$3)) and uspaper; ((grey or gray) same (mask or reticle)) EPO; JPO; IBM_TDB</pre>
bridge same (slop\$3 or inclin\$3 or taper\$3))) not ((resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3)))  - 45 (((resist or photoresist) and (slop\$3 or usPAT; 2004/01/31 17: inclin\$3 or taper\$3)) with (etch\$3)) and us-PGPUB; ((grey or gray) same (mask or reticle)) EPO; JPO; IBM_TDB
taper\$3))) not ((resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3)))  - 45 (((resist or photoresist) and (slop\$3 or USPAT; 2004/01/31 17: inclin\$3 or taper\$3)) with (etch\$3)) and US-PGPUB; ((grey or gray) same (mask or reticle)) EPO; JPO; IBM_TDB
and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3)))  45 (((resist or photoresist) and (slop\$3 or USPAT; 2004/01/31 17: inclin\$3 or taper\$3)) with (etch\$3)) and US-PGPUB; ((grey or gray) same (mask or reticle)) EPO; JPO; IBM_TDB
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<pre>inclin\$3 or taper\$3)) with (etch\$3)) and US-PGPUB; ((grey or gray) same (mask or reticle)) EPO; JPO; IBM_TDB</pre>
((grey or gray) same (mask or reticle)) EPO; JPO; IBM_TDB
IBM_TDB
- 0 ((((resist or photoresist) and (slop\$3 or DERWENT 2003/07/22 15:
inclin\$3 or taper\$3)) with (etch\$3)) and
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- 0 (430/314,323-324.ccls. not ((((resist or DERWENT 2003/07/22 15:
photoresist) and (slop\$3 or inclin\$3 or
taper\$3)) with (etch\$3)) and ((grey or
gray) same (mask or reticle)))) not us.pc.

_	26	((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or	USPAT; US-PGPUB; EPO; JPO;	2004/01/31 17:10
		reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same	IBM_TDB	
-	3048	(photomask or mask or reticle))) 430/314,323-324.ccls. not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or	USPAT; US-PGPUB; EPO; JPO;	2004/01/31 17:11
		gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same	IBM_TDB	
		<pre>(etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or</pre>		
		<pre>inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))))</pre>		
	36	((mems or moems or microelectromechanical or micro adj electromechanical).ti.ab.) and (microbeam or microplatform or microsupport or (suspend\$3 with	USPAT; US-PGPUB; EPO; JPO;	2004/01/31 17:11
	915	microstructure))	IBM_TDB	2003/07/22 15:40
_	915	(((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/07/22 13:40
		430/314,323-324.ccls.) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))		
_	18	resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/07/22 15:40
_	. 36	430/314,323-324.ccls. and (planarization adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with	USPAT; US-PGPUB; EPO; JPO;	2003/07/22 15:41
		<pre>(etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3 or</pre>	IBM_TDB	
		<pre>inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist)))</pre>		
		<pre>and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))))</pre>		
_	11	(resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3))	USPAT; US-PGPUB; EPO; JPO;	2003/07/22 15:41
_	1	((resist or photoresist) and ((microplatform or suspend\$3) same (slop\$3 or inclin\$3 or taper\$3))) and ((grey or	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2003/07/22 15:41
_	2	gray) with mask)	IBM_TDB USPAT; US-PGPUB;	2003/07/22 16:18
			EPO; JPO; IBM_TDB	

			,	
-	17	(((slop\$3 or inclin\$3 or taper\$3) with	USPAT;	2003/07/22 15:43
		(etch\$3)) and 430/320.ccls.) not	US-PGPUB;	
		((((resist or photoresist) and (slop\$3 or	EPO; JPO;	
		inclin\$3 or taper\$3)) with (etch\$3)) and	IBM_TDB	
		((grey or gray) same (mask or reticle)))		
		not (((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same		
		(etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not		
		((((resist or photoresist) and (slop\$3 or		
		inclin\$3 or taper\$3)) with (etch\$3)) and		
		((grey or gray) same (photomask or mask or		
		reticle)))) not (430/314,323-324.ccls. not		
		((((resist or photoresist) and (slop\$3 or		
		inclin\$3 or taper\$3)) with (etch\$3)) and		
		((grey or gray) same (photomask or mask or	İ	
		reticle))) not (((((resist or photoresist)		
		and (slop\$3 or inclin\$3 or taper\$3)) same		
		(etch\$3)) and ((grey or gray) same		
		(photomask or mask or reticle))) not		
		((((resist or photoresist) and (slop\$3 or		
		inclin\$3 or taper\$3)) with (etch\$3)) and		
		((grey or gray) same (photomask or mask or		
}		reticle))))) not (((mems or moems or	-	
		microelectromechanical or micro adj		
		electromechanical).ti.ab.) and (microbeam		
		or microplatform or microsupport or		
		(suspend\$3 with microstructure))) not		
		((((photolithograph\$6 or lithograph\$6 or		1
		photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or		
		205/122-123,125).ccls.) not		
		430/314,323-324.ccls.) not (((resist or		13
		photoresist) and (slop\$3 or inclin\$3 or		1.0
		taper\$3)) with (etch\$3)) and ((grey or		
		gray) same (mask or reticle)))) not		
		(resistive adj evaporat\$3 and		
		((photolithograph\$6 or photoresist or		
		resist) same etch\$3)) not		
		(430/314,323-324.ccls. and (planarization		10
		adj layer) not ((((resist or photoresist)		1.7
		and (slop\$3 or inclin\$3 or taper\$3)) with		
		(etch\$3)) and ((grey or gray) same		
		(photomask or mask or reticle))) not		
		(((((resist or photoresist) and (slop\$3 or		
		inclin\$3 or taper\$3)) same (etch\$3)) and		
		((grey or gray) same (photomask or mask or		
		reticle))) not ((((resist or photoresist)		
		and (slop\$3 or inclin\$3 or taper\$3)) with		
		(etch\$3)) and ((grey or gray) same (photomask or mask or reticle))))) not		
		((resist or photoresist) and (air adj		
		bridge same (slop\$3 or inclin\$3 or		
		taper\$3))) not ((resist or photoresist)		
		and ((microbeam) same (slop\$3 or inclin\$3		
		or taper\$3)))		
-	53	(((resist or photoresist) and (slop\$3 or	USPAT;	2004/04/20 17:01
		inclin\$3 or taper\$3)) with (etch\$3)) and	US-PGPUB;	
		((grey or gray) same (mask or reticle))	EPO; JPO;	
			IBM_TDB	4 4 1
-	30	((((resist or photoresist) and (slop\$3 or	USPAT;	2004/04/20 17:01
		inclin\$3 or taper\$3)) same (etch\$3)) and	US-PGPUB;	
		((grey or gray) same (photomask or mask or	EPO; JPO;	
		reticle))) not ((((resist or photoresist)	IBM_TDB	
		and (slop\$3 or inclin\$3 or taper\$3)) with		
		(etch\$3)) and ((grey or gray) same		
		(photomask or mask or reticle)))	1	1

-	3204	430/314,323-324.ccls. not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/20 16:30
-	43	<pre>((mems or moems or microelectromechanical or micro adj electromechanical).ti.ab.) and (microbeam or microplatform or microsupport or (suspend\$3 with microstructure))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/20 16:29
	955	(((photolithograph\$6 or lithograph\$6 or photoresist or resist) and etch\$3 and (204/192.14-192.15,192.17,192.23,192.25 or 205/122-123,125).ccls.) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (mask or reticle)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/20 16:24
_	19	resistive adj evaporat\$3 and ((photolithograph\$6 or photoresist or resist) same etch\$3)	USPAT; US-PGPUB	2004/04/20 16:23
_	36	430/314,323-324.ccls. and (planarization adj layer) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not (((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) same (etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not ((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and ((grey or gray) same (photomask or mask or reticle)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/20 16:22
-	13	<pre>(resist or photoresist) and (air adj bridge same (slop\$3 or inclin\$3 or taper\$3))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/04/20 16:20
-	1	<pre>((resist or photoresist) and ((microplatform or suspend\$3) same (slop\$3 or inclin\$3 or taper\$3))) and ((grey or gray) with mask)</pre>	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/04/20 16:20
_	3	(resist or photoresist) and ((microbeam) same (slop\$3 or inclin\$3 or taper\$3))	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/04/20 16:19

18 (((slop\$3 or inclin\$3 or taper\$3) with	USPAT;	2004/04/20 16:19
(etch\$3)) and 430/320.ccls.) not	US-PGPUB;	
((((resist or photoresist) and (slop\$3 or	EPO; JPO;	
inclin\$3 or taper\$3)) with (etch\$3)) and	IBM_TDB	
((grey or gray) same (mask or reticle)))	_	1
not (((((resist or photoresist) and		1
(slop\$3 or inclin\$3 or taper\$3)) same		
(etch\$3)) and ((grey or gray) same		
(photomask or mask or reticle))) not	İ	
((((resist or photoresist) and (slop\$3 or		
inclin\$3 or taper\$3)) with (etch\$3)) and		
((grey or gray) same (photomask or mask or		
reticle)))) not (430/314,323-324.ccls. not		
((((resist or photoresist) and (slop\$3 or		
inclin\$3 or taper\$3)) with (etch\$3)) and		
((grey or gray) same (photomask or mask or		
reticle))) not (((((resist or photoresist)		
and (slop\$3 or inclin\$3 or taper\$3)) same		
<pre>(etch\$3)) and ((grey or gray) same (photomask or mask or reticle))) not</pre>		
<pre>((((resist or photoresist) and (slop\$3 or inclin\$3 or taper\$3)) with (etch\$3)) and</pre>		
((grey or gray) same (photomask or mask or		
reticle))))) not (((mems or moems or		
microelectromechanical or micro adj		
electromechanical).ti.ab.) and (microbeam		
or microplatform or microsupport or		
(suspend\$3 with microstructure))) not		
((((photolithograph\$6 or lithograph\$6 or		
photoresist or resist) and etch\$3 and		
(204/192.14-192.15,192.17,192.23,192.25 or		
205/122-123,125).ccls.) not		
430/314,323-324.ccls.) not ((((resist or		
photoresist) and (slop\$3 or inclin\$3 or		
taper\$3)) with (etch\$3)) and ((grey or		
gray) same (mask or reticle)))) not		
(resistive adj evaporat\$3 and		
((photolithograph\$6 or photoresist or		
resist) same etch\$3)) not		
(430/314,323-324.ccls. and (planarization		
<pre>adj layer) not ((((resist or photoresist)</pre>		
and (slop\$3 or inclin\$3 or taper\$3)) with		
(etch\$3)) and ((grey or gray) same		1
(photomask or mask or reticle))) not		
(((((resist or photoresist) and (slop\$3 or		
inclin\$3 or taper\$3)) same (etch\$3)) and		
((grey or gray) same (photomask or mask or		
reticle))) not ((((resist or photoresist)		
and (slop\$3 or inclin\$3 or taper\$3)) with		
(etch\$3)) and ((grey or gray) same		
(photomask or mask or reticle))))) not		
((resist or photoresist) and (air adj		
bridge same (slop\$3 or inclin\$3 or		
taper\$3))) not ((resist or photoresist)		
and ((microbeam) same (slop\$3 or inclin\$3		
or taper\$3)))		